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AUG 23 2001
TC 2800 MAIL ROOM XX

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:

Yutaka SUENAGA et al.

Appln. No.: 09/615,081

Group Art Unit: 2872

Filed: July 12, 2000

Examiner: J. Treas

For: CATADIOPTRIC OPTICAL SYSTEM AND EXPOSURE APPARATUS

EQUIPPED WITH THE SAME

AMENDMENT

Assistant Commissioner for Patents Washington, D.C. 20231

Sir:

In response to the Office Action dated April 19, 2001, please amend the above-identified patent application as indicated below.

IN THE SPECIFICATION:

Please substitute the following paragraph for the paragraph beginning on page 8 at line 21:

01

a catadioptric optical system for projecting said predetermined pattern of said mask disposed on said first surface onto a photosensitive substrate disposed on said second surface.